

WORKSHOP: Fundamentals of Plasma Processing (Etching and Deposition) Date: 25 April 2014 Location: Shanghai Jiao Tong University Room 3-200 SEIEE Building, 800 Dong Chuan Rd, Shanghai 地址: 上海市闵行区东川路 800 号电院群楼 3 号楼 200 室

Plasma-Therm, a leading manufacturer of plasma based etching and deposition equipment, is providing a workshop on the fundamentals of plasma etching and deposition. Lectures will include the basics of plasma reactors and mechanisms for etching and deposition. The workshop will review state of the art etching and deposition technologies as applied to semiconductor, MEMS, and nanofabrication. Talks will cover compound semiconductor, dielectric, and deep silicon etching as well as PECVD and high density plasma CVD of silicon based materials. Fundamental and new ideas for endpoint detection and sample thermal budget management will be presented.

For questions, please contact:

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REGISTRATION: Event is free. Pre-registration is requested. Register online by 18 April 2014

> 上海交通大學 Shanghai Jiao Tong University

http://www.planetReg.com/E2198184518523

Speaker Information: David Lishan, Principal Scientist, Ph.D. David Lishan received his Bachelor's degree in Chemistry from UC, Santa Cruz and M.S. and Ph.D. from UC, Santa Barbara in Solid State Electrical Engineering. During his career he has worked and published on a wide range of material, semiconductor, and chemistry R&D projects in the areas of photochemistry, x-ray mask fabrication, PVD, and plasma processing. He joined Plasma-Therm nearly 15 years ago and currently holds the positions of Principal Scientist and Director in the Technical Marketing Group. His primary focus is on the application of plasma processing for MEMS, photonics, data storage, and compound semiconductor applications.

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